

IN THE CLAIMS:

Please CANCEL claims 1-15 without prejudice to or disclaimer of the recited subject matter.

Please ADD new claims 16-25, as follows. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

1-15. (Cancelled)

16. (New) An anti-vibration apparatus comprising:

a table;

a pneumatic spring for applying a force to said table;

an electromagnetic actuator for applying a force to said table; and

a first generator which generates a driving signal for said electromagnetic actuator based on at least one of a target position and a target speed with respect to a movable object on said table.

17. (Original) An apparatus according to claim 16, further comprising a second generator which generates a signal for changing a pressure in said pneumatic spring based on at least one of the target position and the target speed.

18. (Original) An apparatus according to claim 16, wherein said first generator includes a filter which filters a signal with respect to at least one of the target position and the target speed.

19. (Original) An apparatus according to claim 18, wherein a cutoff frequency of said filter has a value within a controllable frequency range of said pneumatic spring.

20. (Original) An apparatus according to claim 17, wherein said second generator includes a filter which filters a signal with respect to at least one of the target position and the target speed.

21. (Original) An apparatus according to claim 20, wherein a cutoff frequency of said filter has a value within a controllable frequency range of said pneumatic spring.

22. (Original) An exposure apparatus for exposing a substrate to a pattern, said apparatus comprising an anti-vibration apparatus defined in claim 16.

23.. (Original) An apparatus according to claim 22, further comprising a movable stage as the movable object.

24. (Original) A device manufacturing method comprising:

a step of exposing a substrate to a pattern using an anti-vibration apparatus defined in claim 16.

25. (Original) A device manufacturing method comprising:

a step of exposing a substrate to a pattern using an exposure apparatus defined in claim 22.